



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Zhang et al.

Serial Number:

10/696,326

Filed:

October 29, 2003

Group Art Unit:

1756

Examiner:

Unassigned

Title:

Photomask Assembly and Method for Protecting the Same from Contaminants during a Lithography Process

EV352394615US

MAIL STOP - AMENDMENT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

I hereby certify that this Information Disclosure Statement is being deposited with the United States Postal Service as Express Mail : EV352394615US addressed to: Mail Stop - Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on October 15, 2004.


Angela Loding

INFORMATION DISCLOSURE STATEMENT

Applicants respectfully request, pursuant to 37 C.F.R. §§1.56, 1.97 and 1.98, that the references listed on the enclosed PTO-1449 form be considered and cited in the examination of the above-identified application. Since the present Application was filed after June 30, 2003, a copy of any U.S. Patent cited on the attached PTO Form 1449 is not being submitted with this Information Disclosure Statement pursuant to the July 11, 2003 waiver of 37 C.F.R. §1.98(A)(2)(i) by the U.S. Patent and Trademark Office. Furthermore, pursuant to 37 C.F.R. §§1.97(g) and (h), no representation is made that these references are material to the patentability of the present application.

Applicants believe no fees are due, however, the Commissioner is hereby authorized to charge any fees or credit any overpayments to Deposit Account No. 50-2148 of Baker Botts L.L.P.

Respectfully submitted,
BAKER BOTTS L.L.P.
Attorneys for Applicants


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Date: October 15, 2004

PTO-1449 Information Disclosure Citation in an Application	OCT 15 2004	Application No. 10/696,326	Applicant(s) Zhang et al.		
		Docket Number 064441.0266	Group Art Unit 1756	Filing Date 10/29/2003	

U.S. PATENT DOCUMENTS

	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
A.	3927943	12/23/75	Pohl et al.	355	132	07/01/74
B.	4032233	06/28/77	Oscarsson et al.	355	91	05/03/76
C.	4131363	12/26/78	Shea et al.	355	75	12/05/77
D.	4159176	06/26/79	de Masi	355	79	11/14/77
E.	4255216	03/10/81	Conant et al.	156	80	01/14/80
F.	4470508	09/11/84	Yen	206	334	08/19/83
G.	4536240	08/20/85	Winn	156	74	02/22/83
H.	4584216	04/22/86	Kenworthy et al.	428	38	06/15/84
I.	4657805	04/14/87	Fukumitsu et al.	428	215	06/13/85
J.	4737387	04/12/88	Yen	428	14	07/07/86
K.	4833051	05/23/89	Imamura	430	5	12/17/87
L.	4948851	08/14/90	Squire	526	247	12/28/89
M.	4973142	11/27/90	Squire	350	409	04/09/90
N.	5008156	04/16/91	Hong	428	506	12/06/98
O.	5061024	10/29/91	Keys	359	350	09/06/89

FOREIGN PATENT DOCUMENTS

	DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	
P.	2000292909	10/20/00	JP (abstract only)	G03F	1/14	X	
Q.	10062966	03/06/98	JP (abstract only)	G03F	1/14	X	

NON-PATENT DOCUMENTS

	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
R.	International PCT Search Report with Notification of Transmittal, PCT/US03/34485, 8 pages.	Mailed 07/29/04
S.	Bernal, M.P. et al., "Natural Zeolites and Sepiolite as Ammonium and Ammonia Adsorbent Materials", Bioresource Technology 43 (1993) pp. 27-33.	1993
T.	Bernal, M.P. et al., "Application of Natural Zeolites for the Reduction of Ammonia Emissions during the Composting of Organic Wastes in a Laboratory Composting Simulator", Bioresource Technology 43 (1993) pp. 35-39.	1993
U.	Grayfer et al., "Protecting 248 nm Lithography from Airborne Molecular Contamination during Semiconductor Fabrication", Proceedings of SPIE Vol. 4346 (2001), pp. 676-694. Optical Microlithography XIV.	2001

EXAMINER	DATE CONSIDERED
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.	

PTO-1449 Information Disclosure Citation in an Application	Application No.	Applicant(s)		
	10/696,326	Zhang et al.		
	Docket Number	Group Art Unit	Filing Date	
	064441.0266	1756	10/29/2003	

U.S. PATENT DOCUMENTS

	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
A.	5260585	11/09/93	Tom	250	573	06/12/92
B.	5487771	01/30/96	Zeller	55	523	07/27/94
C.	5723860	03/03/98	Hamada et al.	250	239	06/28/96
D.	5856018	01/05/99	Chen et al.	428	448	06/17/96
E.	5928410	07/27/99	Jois et al.	95	51	12/09/97
F.	6083577	07/04/00	Nakagawa et al.	428	14	03/17/98
G.	6149992	11/21/00	Nakayama	428	14	10/19/98
H.	6254942	07/03/01	Tanaka	428	14	06/07/00
I.	6277342	08/21/01	Pearlstein et al.	423	210	08/23/99
J.	6383258	05/07/02	Simmons	95	45	12/19/00
K.	6395066	05/28/02	Tanihara et al.	95	47	02/23/00
L.	6428583	08/06/02	Reuter	23	301	04/27/00

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	DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
M.	2001350252	12/21/01	JP (abstract only)	G03F	1/14	X	
N.	04196117	07/15/92	JP (abstract only)	H01L	21/027	X	
O.	10198021	07/31/98	JP (abstract only)	G03F	1/14	X	
P.	01/59522 A1	08/16/01	WO	G03F	1/14	X	
Q.	2004/031855 A2	04/15/04	WO	G03F	--	X	
R.							
S.							

NON-PATENT DOCUMENTS

	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
T.	Kinlead et al., "Targeting Gaseous Contaminants in Wafer FABs: Fugitive Amines", Microcontamination, pp. 37-40.	06/1993
U.	Cullins et al., "157-nm Photomask Handling and Infrastructure: Requirements and Feasibility", Proceedings of SPIE Vol. 4409 (2001), pp. 632-640, Photomask and Next-Generation Lithography Mask Technology VIII; XP-002287329	2001

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		DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	A.	6433356	08/13/02	Cahen et al.	257	40	07/14/99
	B.	6435586	08/20/02	Getzschman et al.	296	37.6	04/13/01
	C.	6436586	08/20/02	Matsuoka et al.	430	5	04/06/00
	D.	6443302	09/03/02	Tanaka	206	316.1	04/26/01
	E.	6444608	09/03/02	Oki et al.	502	300	10/17/01
	F.						
	G.						
	H.						
	I.						
	J.						
	K.						
	L.						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
							YES
	M.						
	N.						
	O.						

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